

**RETICLE CHUCKS AND METHODS FOR HOLDING A LITHOGRAPHIC
RETICLE UTILIZING SAME**

Abstract of the Disclosure

5 Reticle-holding devices ("reticle chucks") are disclosed that define a
downstream-facing reticle-mounting surface configured for holding an upstream-
facing surface of a reticle for use in a microlithography apparatus. The reticle
chucks can include peripheral regions and struts that define respective portions of
the reticle-mounting surface, thereby preventing reticle sag while still allowing the
10 axial distance from the reticle to a projection-optical system to be measured by
grazing incidence without obstruction. The reticle can be held by, e.g., electrostatic
attraction or vacuum suction to the reticle-mounting surface. The subject chucks
also can be used for holding a reticle blank while inscribing a pattern on the reticle
15 blank.

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